

REMARKS

The Office Action mailed April 11, 2005, has been received and reviewed. Claims 1 through 21 are currently pending in the application. Claims 1- 17 are allowed. Claims 18 through 21 stand rejected. Applicant has canceled claim 20 and incorporated part of claim 20 in claim 18. Reconsideration is respectfully requested.

35 U.S.C. § 102(b) Anticipation Rejections

Anticipation Rejection Based on U.S. Patent No. 5,332,646 to Wright et al.

Claims 18 through 20 stand rejected under 35 U.S.C. § 102(b) as being anticipated by Wright et al. (U.S. Patent No. 5,332,646). Applicant respectfully traverses this rejection, as hereinafter set forth.

A claim is anticipated only if each and every element as set forth in the claim is found, either expressly or inherently described, in a single prior art reference. *Verdegaal Brothers v. Union Oil Co. of California*, 2 USPQ2d 1051, 1053 (Fed. Cir. 1987). The identical invention must be shown in as complete detail as is contained in the claim. *Richardson v. Suzuki Motor Co.*, 9 USPQ2d 1913, 1920 (Fed. Cir. 1989).

Applicant respectfully submits that Wright fails to disclose, either expressly or inherently, every element of claim 18 of the presently claimed invention. Claim 18 recites an “electroless plating bath for depositing an oxidation barrier on a semiconductor device structure, the bath comprising at least one metal salt and at least one of dimethylamineborane and potassium borohydride.” Applicant respectfully submits that Wright fails to disclose the presence of dimethylamineborane or potassium borohydride. As Wright fails to disclose every element of the presently claimed invention, claim 18 is allowable.

Claim 19 is allowable as depending directly from allowable claim 18.

Anticipation Rejection Based on U.S. Patent No. 4,329,207 to Maruta

Claims 18, 20 and 21 stand rejected under 35 U.S.C. § 102(b) as being anticipated by Maruta (U.S. Patent No. 4,329,207). Applicant respectfully traverses this rejection, as

hereinafter set forth.

Applicant respectfully submits that Maruta fails to disclose, either expressly or inherently, every element of claim 18 of the presently claimed invention. Claim 18 recites an “electroless plating bath for depositing an oxidation barrier on a semiconductor device structure, the bath comprising at least one metal salt and at least one of dimethylamineborane and potassium borohydride.” Applicant respectfully submits that Maruta fails to disclose the presence of dimethylamineborane or potassium borohydride. As Maruta fails to disclose every element of the presently claimed invention, claim 18 is allowable.

Claims 19 and 21 are allowable as depending from allowable claim 18.

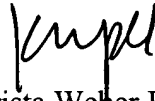
ENTRY OF AMENDMENTS

The amendments to the claims above should be entered by the Examiner because the amendments are supported by the as-filed specification and drawings and do not add any new matter to the application. Further, the amendments do not raise new issues or require a further search.

CONCLUSION

Claims 1-19 and 21 are believed to be in condition for allowance, and an early notice thereof is respectfully solicited. Should the Examiner determine that additional issues remain which might be resolved by a telephone conference, he is respectfully invited to contact Applicant's undersigned attorney.

Respectfully submitted,



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